



SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

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055071-0267SERIAL NO.
10/626,858APPLICANT
Stephen D. HSU, et al.FILING DATE
July 25, 2003GROUP
2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
SP		US 6,851,103 B2	Feb. 1, 2005	Van Den Broeke et al.	
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						Yes	No
SP		EP 1 091 252 A2	04-11-2001			X	
SP		EP 1 152 289 A2	11-07-2001			X	
SP		EP 1 152 289 A3	11-07-2001			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
SP		"Mask Topography Effects in Projection Printing of Phase-Shifting Masks", Alfred K. Wong and Andrew R. Neureuther, Fellow, IEEE Transactions on Electron Devices, Vol. 41, No. 6, June 1994
SP		"Spatial Frequency Doubling Lithography (SFDL) of Periodic Structures for Integrated Optical Circuit Technology", Tanya E. Jewell and Donald L. White. Journal of Lightwave Technology, Vol. 7, No. 9, September 1989

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/Suchin Parihar/DATE CONSIDERED
06/29/2006

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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